

Notice of References Cited		Application/Control No.	Applicant(s)/Patent Under Reexamination	
		10/666,601	LOBO ET AL.	
Examiner Kimberly Lovel		Art Unit 2167	Page 1 of 1	

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-2005/0131861	06-2005	Arritt et al.	707/001
*	B	US-2003/0069795	04-2003	Boyd et al.	705/22
*	C	US-2004/0243580	12-2004	Markki et al.	707/009
*	D	US-6,484,173	11-2002	O'Hare et al.	707/9
*	E	US-6,807,542	10-2004	Bantz et al.	707/9
*	F	US-6,105,027	08-2000	Schneider et al.	707/9
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Cho, Jung Won. "Pulsed DC Reactive Magnetron Sputtering of Alluminum Nitride Thin Films." North Carolina State University: 8/272002, pages 1, 36, 151 and 153. http://www.lib.ncsu.edu/theses/available/etd-08/27/2002-151641/unrestricted/etd.pdf
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.